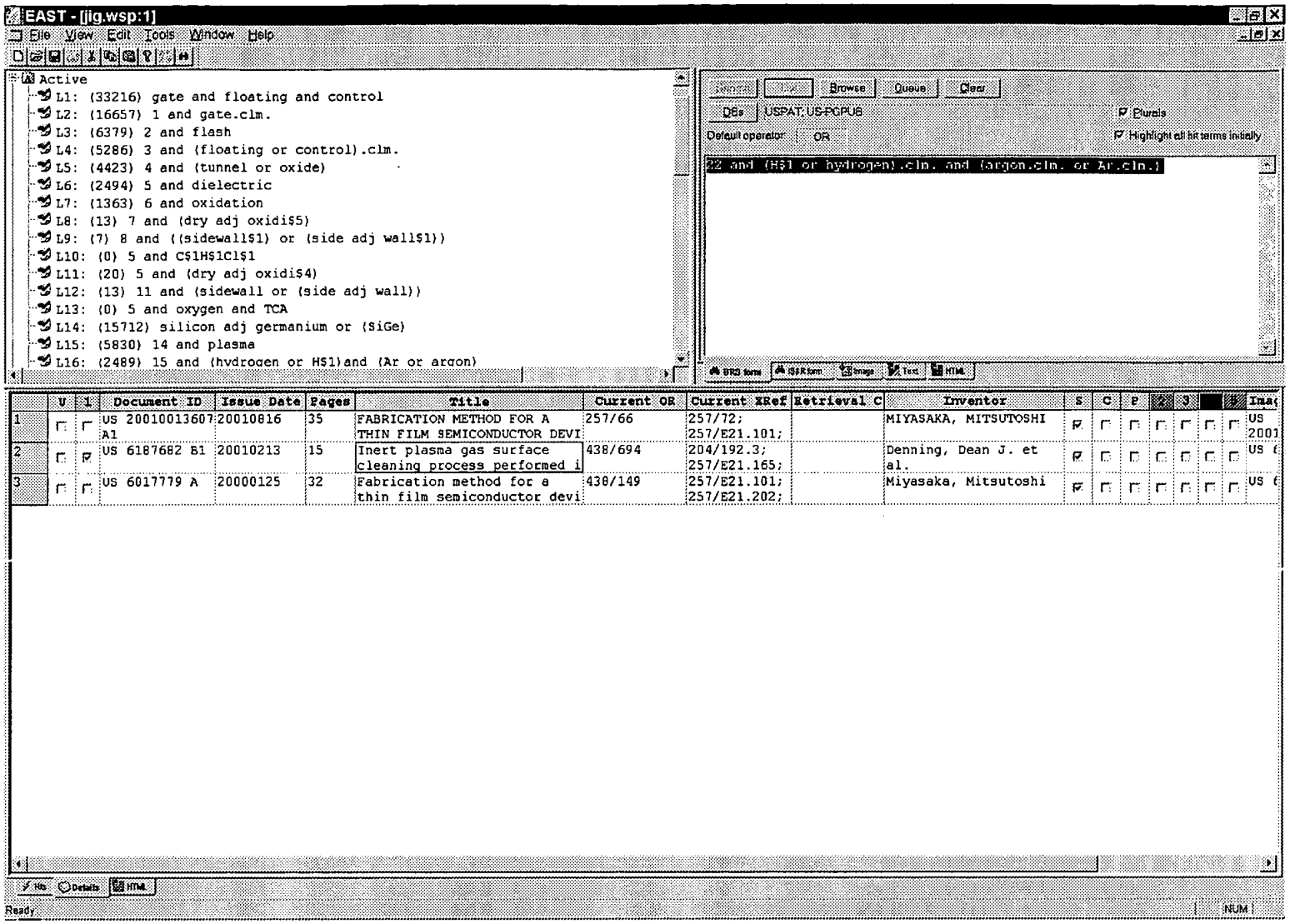

	U	1	Document ID	Issue Date	Pages	Title	Current OR	Current XRef	Retrieval C	Inventor	S	C	P	2	3		#	Ima
1	☐	☐	US 20010013607 A1	20010816	35	FABRICATION METHOD FOR A THIN FILM SEMICONDUCTOR DEVI	257/66	257/72; 257/E21.101;		MIYASAKA, MITSUTOSHI	☑	☐	☐	☐	☐	☐	☐	US 2001
2	☐	☑	US 6187682 B1	20010213	15	Inert plasma gas surface cleaning process performed i	438/694	204/192.3; 257/E21.165;		Denning, Dean J. et al.	☑	☐	☐	☐	☐	☐	☐	US 6
3	☐	☐	US 6017779 A	20000125	32	Fabrication method for a thin film semiconductor devi	438/149	257/E21.101; 257/E21.202;		Miyasaka, Mitsutoshi	☑	☐	☐	☐	☐	☐	☐	US 6